Structural, Topographical and Optoelectronic Properties of ZnIn$_2$S$_4$ Thin Films Deposited from Dual Source Using Aerosol Assisted Chemical Vapour Deposition (AACVD) Technique

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Summary: The ZnIn$_2$S$_4$ (ZIS) thin films have been successfully developed from a homogeneous tolune solution of dithiocarbarnate complexes of zinc and iodium with formula [Zn(S$_2$CN(C$_2$H$_5$)$_2$)(py)] (1) and [In(S$_2$CN(C$_2$H$_5$)$_2$)$_2$py] (2) via aerosol assisted chemical vapor deposition (AACVD) technique. Deposition experiments were carried out at 500°C in an inert atmosphere of argon gas on FTO substrate. The X-ray diffraction (XRD), X-ray photoelectron spectroscopy (XPS), field emission scanning electron microscopy (FESEM) and Raman spectroscopy have been used for the determination of phase purity, surface topography of the uniformly distributed particles and oxidation states of the elements present in thin films. Further UV-visible spectrophotometry elucidates that the thin films absorbs in entire visible region and give estimated band gap energy of 2.37 eV. The photoelectrochemical (PEC) response in terms of linear scan voltammetry (LSV) provides a photocurrent density 2.27 mA cm$^{-2}$ at 0.7 V vs Ag/AgCl/3M KCl using 0.05 M sodium sulphide solution under AM 1.5 G illumination (100 mW cm$^{-2}$). The LSV results are further reinforced by electrochemical impedance spectroscopy (EIS) that gives charge transfer resistance ($R_t$) value of 5.7 x 10$^4$ Ω under dark conditions and reduces to 3.7 x 10$^4$ Ω under illumination.

Keyword: ZnIn$_2$S$_4$; Thin film; Photo oxidation of water; Band gap; Photoconductivity.

Introduction

The story of photocatalyst began with the development of titanium oxide (TiO$_2$) back in 1972. Since then photocatalyst technology has been used as an alternative energy source for natural resources [1-3]. This technology helps to generate hydrogen by photolytic water splitting and also serves as green energy source by destroying pollutants in water under normal conditions of temperature and pressure [4, 5]. Numerous metal oxides and metal sulphides had been synthesized and applied as photocatalyst in past but the later has an advantage due to high conduction band value and utilization of visible portion of solar spectrum [6-8]. Therefore, metal sulphide are best choice for scientists due to better visible and UV radiation response[9-11].

Owing to semiconducting nature, low band gap of 2.3-2.5 eV and chemical stability, ZnIn$_2$S$_4$ has gained much attention towards exploring new grounds in field of solar cell applications and photooxidation of water for hydrogen production [11-17]. Moreover, ZnIn$_2$S$_4$ is a ternary chalcogenide semiconductive material having layered alignment and finds extensive functions in optical and photoconductive devices [18-24]. Various ZnIn$_2$S$_4$ nanostructures and microstructures, such as, nanoribbon, nanotubes, nanoplate, sub microsphere and nanowire have been synthesized via different techniques [13, 23, 25-31]. But still tailoring of ZnIn$_2$S$_4$ thin films with nanostructure and uniform distribution is a big challenge that bounds their utilization in photovoltaic devices. Various physical and chemical methods with their own pros and cons have been used for deposition of ZnIn$_2$S$_4$ thin films. These techniques involve MOCVD [32], SILAR [33], hydrothermal method [18], electrodeposition [34], chemical bath deposition [35], atomic layer deposition [36], microwave assisted synthesis [37], spin coating method [38] and spray pyrolysis method.[39] Due to some limitations pertaining to afore mentioned techniques such as utilization of expensive instruments, requisite of line of sight between source and substrate, requirement of high vacuum, low deposition rate, low morphological control, low purity of product, difficulty in
controlling metal ions ratio, etc.[40], we therefore, focused on developing the thin films via AACVD.

The thin film deposition technique (AACVD) using single and mixed molecular precursors attracted the attention of researchers in recent years as this method is simple and scalable. Moreover, particle size and morphology of the deposited thin films can easily be controlled by varying different parameters such as deposition temperature, solvent choice and frequency of ultrasonic modulator[41]. Many nano scaled thin films of metal sulphide using single source metal dithiocarbamate precursor have been synthesized and reported in past few years such as indium sulphide [42], zinc sulphide[43], cadmium sulphide[44], bismuth sulphide[45] and silver sulphide[46]. Recently AACVD technique has been used to fabricate ZnO thin films on FTO glass substrate [47-48]. But deposition of ZnIn$_2$S$_4$ thin films by AACVD is not reported to date. Since both the precursors (1) and (2) have very similar salivation and thermal properties [42, 43], therefore we were prompted to synthesize ZnIn$_2$S$_4$ using their (1:2) solution in toluene to fabricate thin films on FTO substrate at 500°C. The synthesized ZnIn$_2$S$_4$ thin films were characterized by XRD, XPS, EDX, FESEM, Raman and UV-Vis spectroscopy for their crystallinity, structure, topographic morphology, oxidation state of elements involved, phase purity, and optical band gap values. Moreover, photoconductive characteristics of fabricated ZnIn$_2$S$_4$ thin films measured by linear scan voltammetry and supported by impedance results, confirmed that the films are active for solar light harvesting applications.

**Experimental**

*Synthesis of [Zn(S$_2$CNCy$_2$)$_2$(py)] (1) and [In(S$_2$CNCy$_2$)$_3$].2py (2)*

The precursor complexes [Zn(S$_2$CNCy$_2$)$_2$(py)] (1) and [In(S$_2$CNCy$_2$)$_3$].2py (2) were synthesized by following the reported procedure as described below[42, 43].

The 0.75 g (2.7 mmol) of purified crystals of Na(S$_2$CNCy$_2$) were dissolved in chloroform in a round bottom flask fitted with a reflux condenser, a dropping funnel and inert gas line. To this stirring solution was added about 0.18 g (1.32 mmol) of zinc chloride that made the solution turbid. After half an hour stirring, pyridine was added drop wise to this turbid mixture that resulted in a clear solution. After 2 hours stirring the solution was kept for crystallization in the fume hood, that yielded colorless crystals of [Zn(S$_2$CNCy$_2$)$_2$(py)] (1) after evaporation of solvent. 2 Same procedure was applied for the synthesis of indium complex, except that in synthesis of (2) methanol was used as solvent rather than chloroform and 0.195 g (0.9 mmol) of indium trichloride was used to get colorless crystals of [In(S$_2$CNCy$_2$)$_3$].2py (2).1

**Fabrication of thin films**

The ZnIn$_2$S$_4$ thin films were fabricated from [Zn(S$_2$CNCy$_2$)$_2$(py)] (1) and [In(S$_2$CNCy$_2$)$_3$].2py (2) at 500 °C on FTO glass substrate via AACVD technique explained elsewhere.1 The FTO coated glass substrate with dimension 25.4 x 12.7 x 2.2 mm (L x W x D) and surface resistivity of 7 Ω/sq were ultrasonically cleaned with ethanol and acetone and finally rinsed with distilled water prior to fabricate the thin films. In normal deposition procedure, 0.1 g (0.152 mmol) of [Zn(S$_2$CNCy$_2$)$_2$(py)] (1) and 0.316 g (0.303 mmol) of [In(S$_2$CNCy$_2$)$_3$].2py (2) were dissolved in 10 ml toluene solvent and then transferred to a 50 ml round-bottomed flask associated with deposition arrangements. The FTO substrates were placed in a reactor tube and argon as a carrier gas was flow at rate of 100 mL.min$^{-1}$. The temperature of substrates inside reactor tube was adjusted to 500 °C about ten minutes before the agitation of precursor solution for aerosol generation. A piezoelectric modulator of an ultrasonic humidifier was used to agitate the precursor’s solution in a round bottom flask to produce the aerosols. The carrier gas then moved the aerosol to hot reactor tube where aerosols decomposed to produce targeted ZIS thin films on FTO substrates. The total time for deposition of film was 40 minutes. During the experiment the exhaust and volatiles from the reactor tube was extracted into extraction system inside fuming hood. Finally, the films were allowed to cool at room temperature under continuous flow of argon gas, prior to use them for characterization and PEC studies. The deposition experiment was repeated several times to confirm the reproducibility of fabricated films.

**Characterization of Materials**

Field emission gun electron microscope, FESEM (FEI Quanta 400) integrated with energy dispersive X-rays spectrometer (EDX-INCA Energy 200) was used to evaluate elemental composition and morphological aspects of ZIS thin films under controlled settings of accelerating voltage (20 kV) with a working distance (9.2 mm). The PAN analytical diffractometer (X’Pert High Score) with high intensity monochromatic radiation of Cu-K$a$ having wavelength (λ) 1.5418 Å was employed to
elucidate crystalline phase and crystallinity of synthesized ZIS thin films. In order to screen all conceivable reflection peaks, the test materials (Thin films) were scanned from $10^\circ$ to $60^\circ$ with a step size of $0.026^\circ$ operating at 40 kV and 40 mA. The Raman spectroscopical analysis was performed with Raman microscope (Renishaw InVia) and a beam of argon laser (514 nm) of output power (0.01 mW) was used to excite the samples. The X-ray photo electron spectroscopic (XPS) studies of ZIS thin films were achieved on ULVAC PHI (Quantera II) having monochromatic radiation of Al Ka (1486.8 eV) as X-rays donor operating at 25.6 W. The narrow scan analysis was done by using an energy source of 112 eV with 0.1 eV at every step. The UV-vis spectrophotometer (Lambda 35 Perkin-Elmer) was used to estimate light absorbing capacity (optical absorbance) of fabricated ZIS thin films.

The data were gathered in the wavelength range of 350 to 900 nm applying pure FTO glass substrate as a reference electrode. The thickness of ZnIn$_2$S$_4$ films is determined by using a profilometer KLA Tencore P-6 surface profiler.

The photoelectrochemical (PEC) behavior of ZnIn$_2$S$_4$ thin films was assessed by employing an electrochemical cell consisting of three electrodes and having a quartz window. This standard electrochemical cell uses Ag/AgCl.3M KCl as a reference electrode, platinum wire as a counter electrode and an aqueous solution Na$_2$S (0.01M) as an electrolyte to measure the photoconductive response of ZnIn$_2$S$_4$ films electrodes. The solar simulator AM 1.5 (Solar Light 16S-300 solar simulator) was used to illuminate the cell’s compartment throughout the experiments with intense light of 100 mWcm$^{-2}$ and the operative range of electrodes was 1 cm$^2$. The PEC response interns of steady state current-voltage (I-V Curves) and electrochemical impedance spectroscopy (EIS) was recorded on potentiostat Autolab type III (Eco Chemie micro).

Results and Discussion

The precursors [Zn(S$_2$CNCy$_2$)$_2$(py)] (1) and [In(S$_2$CNCy$_2$)$_2$.2py] (2) are obtained in 75% and 80% yield by double displacement reaction of {Na[S$_2$CNCy$_2$]} with zinc chloride and indium chloride in pyridine-chloroform and pyridine-methanol solvent system, respectively. The synthesized precursors contain pyridine as Lewis base that promotes its stability at room temperature, resistance to air and moisture, and ease of solubility in suitable organic solvents. Furthermore, both of the precursors (1) and (2) are soluble in common organic solvents such as chloroform, THF, pyridine and toluene and give stable sulphide after decomposition at 400 °C and above [42, 49]. Keeping in view these similar dissolution and thermal properties such as decomposition temperature (375 °C for (1) and 340 °C for (2)), ZnIn$_2$S$_4$ thin films were fabricated at 500 °C using the stoichiometric ratio of precursors in toluene solution.

X-Ray Diffraction Studies

Crystalline phase, degree of crystallinity and phase purity of the ZIS thin films fabricated at 500°C on FTO substrate was evaluated by using X-ray diffraction spectroscopy (XRD) and results are depicted in Fig. 1. The XRD pattern obtained is in good agreement with that of hexagonal ZnIn$_2$S$_4$ nanosheets reported by Zhenyi et al [50]. The relative peak positions labelled by (■) at 20 value of 21.1, 26.8, 28.3, 41.2, 47.2, 52.8° belongs to (006), (102), (104), (108), (110) and (116) lattice respect of phase pure ZnIn$_2$S$_4$. Whereas, the remaining peaks marked by (▼) are originated from fluorine doped tin oxide (FTO) substrate and the two peaks at 20 value of 33.6 and 56.2° are shared by both ZnIn$_2$S$_4$ and FTO. The thickness of films is 410 nm as determined by profilometer. It is clear from the diffractogram that we have got better pattern of hexagonal phase of ZnIn$_2$S$_4$ imparts of peak intensities and peak broadening as compared to that of previously reported and this might be attributed to the well-defined and uniform distribution of end product on the surface of substrate as supported by FESEM studies.

![Fig. 1 XRD pattern of ZnIn$_2$S$_4$ thin films fabricated from homogenous solution of precursors (1) and (2) at 500 °C on FTO substrate via AACVD.](image)
XPS Analysis

To verify XRD results, the X-ray photoelectron spectroscopic (XPS) analysis (Fig. 2) was carried out to determine elemental composition and oxidation state of elements present in ZnIn$_2$S$_4$ thin films. The survey scan spectrum (Fig. 2a) confirms that Zn, In and S are major components at the surface of films as indicated by the peaks of binding energies (eV) 87.85, 492.87, 585.03, 1021.66, 1043.44 for Zn, 17.47, 443.95, 452.51, 666.23, 702.88, 1085.28 for In and 161.76, 225.08 for S. The one peak appears at 531 eV is due to the contribution of FTO substrate. Moreover, the atomic ratio of Zn, In and S, provided by XPS is almost 1:2:4 and is good agreement with the results obtained from EDX analysis (ESI Fig. 1†), thereby confirming the fabrication of phase pure ZnIn$_2$S$_4$ thin films.

The narrow scan spectrum of Zn (Fig. 2b), shows peak at 1021.7 eV corresponds to the binding energy of Zn2p$_{3/2}$ [51]. In (Fig. 2c) there appears two peaks at 444.7 eV and 452.3 eV with separation energy of 7.6 eV belong to binding energy of In3d$_{3/2}$ and In3d$_{5/2}$ respectively confirms that indium is present in oxidation state of +3, while the spectrum of Sulphur (Fig. 2d) gives two peaks at 161.3 eV and 162.5 eV that corresponds to binding energy of S2p [52].

Raman Spectroscopy

Further to support XRD and XPS results, ZnIn$_2$S$_4$ thin films were subjected to Raman spectroscopic analysis for its microstructural analysis (Fig. 3). Raman spectroscopical analysis is very good technique to assess the crystallinity of target materials as it offers inelastic distribution of peaks that furnish knowledge about vibration modes of crystalline material. The semiconductive material of good crystallinity presents the more intense Raman modes in comparison to the poor crystalline materials. The Raman spectra of fabricated ZIS thin films (Fig. 3) presents peaks at 248.1(longitudinal mode), 308(transverse mode) and 359.2 cm$^{-1}$(longitudinal mode), which are in very close match with previously reported Raman results of ZnIn$_2$S$_4$ semiconductor[38].
Fig. 3: Raman scattering of ZnIn$_2$S$_4$ thin films fabricated on FTO substrate at 500 °C from toluene solution of precursors (1) and (2) via AACVD.

**Topographical Analysis**

The surface morphology of deposited ZnIn$_2$S$_4$ thin films on FTO substrate at 500°C was determined by using FESEM analysis. The thin film surface morphology (Fig. 4) elucidates uniformly distributed irregular shaped compact particles having well-defined sharp boundaries. The well-connected particles with some voids entirely covered the surface of FTO substrate which can facilitate the electrolyte to penetrate and interact the inner layers of thin film once stimulates by sunlight.

Optical studies

The optical band gap energy of ZnIn$_2$S$_4$ thin film was retrieved from UV-Vis spectrum (Fig 5).

The UV-vis spectrum of thin film shows a steady increase in absorbance while moving towards lower wavelength of light and approaches to its maximum value at 380 nm. The optical band gap ($E_g$) values were obtained from Tauc’s equation:

$$a h v = A (h v - E_g)^\gamma$$

where $a$ is the linear absorption coefficient of the material, $h v$ is the photon energy, $A$ is a proportionality constant and $\gamma$ is a constant depending on the band gap nature; $\gamma = 1/2$ for allowed direct band gap and $\gamma = 2$ for indirect band gap. The direct band gap was calculated by using Tauc's equation arranged as $(a h v)^2 = A_1 (h v - E_g)$. A plot of $(a h v)^2$ versus $h v$ (Inset of Fig. 5) gave a linear region with slope $A_1$ whose extrapolation to $a (h v) = 0$ would yield the value of the direct band gap of 2.37 eV for ZnIn$_2$S$_4$ thin films fabricated at 500 °C from toluene solution of precursors (1) and (2) of FTO substrate. This band gap value is in good agreement with reported values$^{[16]}$.

Fig. 5: UV-Visible spectrum of ZnIn$_2$S$_4$ thin films fabricated on FTO substrate at 500 °C in toluene solution of precursors (1) and (2) and inset is the Tauc’s plot giving optical band gap value of 2.37 eV for ZnIn$_2$S$_4$ thin films.

**Photo-electrochemical Response**

The Linear Scan Voltammetry (LSV) of ZnIn$_2$S$_4$ thin films (Fig. 6), performed in 0.01 M Na$_2$S aqueous solution, produces anodic photocurrent density of 2.27 mA.cm$^{-2}$ at + 0.7 V. It is found that the photocurrent density produced in present studies is higher as compared to the previously reported photocurrent density values of 8 µA.cm$^{-2}$ and 1.5 mA.cm$^{-2}$ for ZnS and In$_2$S$_3$ thin films, respectively. Moreover, it is revealed that this value is also higher
than the previously reported photocurrent density of 0.27 mA.cm\(^{-2}\) and 0.29 mA.cm\(^{-2}\) [33, 38, 39] for single phase ZnIn\(_2\)S\(_4\) produced by different techniques. This improvement in photocurrent density is attributed to uniform distribution of particles with a porous texture. The porous texture of thin film facilitates the electrolyte to penetrate deep into the inner layers and increase the electrode-electrolyte surface interaction. At the same time well-connected particles make an ease to electronic flow.

![Fig. 6 Linear sweep voltammetry (LSV) of ZnIn\(_2\)S\(_4\) thin films fabricated on FTO substrate at 500 °C in toluene solution of precursors (1) and (2) in dark (black) and under light (red).](image)

Moreover, the ZIS thin films were subjected to electrochemical impedance spectroscopical (EIS) analysis in order to get improved vision of interfacial charge transport resistance between electrode face and electrolyte and outcomes are depicted in Fig. 7. The Nyquist plots of ZnIn\(_2\)S\(_4\) thin films under dark and illumination (Fig. 7) showed the equivalent series resistance (R\(_s\)) of device which is obtained when high frequency semicircles intersect the x-axis. Herein, the R\(_s\) value can be overlooked as it remains almost same in light and dark situations due to similar material nature. The simulated semicircles under light and dark (inset of figure 7) provide charge transfer resistance (R\(_{ct}\)) values. It is observed that the R\(_{ct}\) value of ZnIn\(_2\)S\(_4\) thin film decreases significantly from \(5.7 \times 10^4\) Ω to \(3.7 \times 10^4\) Ω after light illumination indicating an ease in electron transport with minimum possibility of the charge recombination, thus delivering enhanced photocurrent density and photoresponse for oxidation of water.

![Fig. 7 Nyquist plot of ZnIn\(_2\)S\(_4\) thin films fabricated on FTO substrate at 500 °C in toluene solution of precursors (1) and (2) in dark (black) and under light (red).](image)

**Conclusions**

In summary, Zinc thioindate thin films are successfully fabricated on FTO substrate at 500 °C from dual source precursors (1) and (2) possessing similar physicochemical properties by Aerosol Assisted Chemical Vapor deposition (AACVD) method and used as photoelectrode. It is found that well connected particles of the thin films with porous texture and a band gap of 2.37 eV provide exceptionally improved photocurrent density of 2.27 mA.cm\(^{-2}\) which was further confirmed by impedance studies. The Nyquist curves show a prominent shift of charge transfer resistance from \(5.7 \times 10^4\) Ω to \(3.7 \times 10^4\) Ω under illumination and approve the improvement in charge transfer under light conditions. These results indicate the utilization of these ternary thin films in photovoltaic and photoelectrochemical devices.

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**Conflict of interest**

The authors have no conflict of interests.
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